Structural Evolution of the Binary System Ba-Si under High-pressure and High-temperature Conditions

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A new silicon-rich binary compound $BaSi_6$ has been prepared by the treatment of the Ba_8Si_{46} clathrate compound under a pressure of 15 GPa at $1000\,^{\circ}$ C, or from a stoichiometric mixture of $BaSi_2$ and Si by treatment under similar high-pressure and high-temperature conditions. The Rietveld refinements revealed that $BaSi_6$ is isomorphous with $EuGa_2Ge_4$, and crystallizes with space group *Cmcm* and the lattice parameters a=4.485(1), b=10.375(2), and $c=11.969(3)\,^{\circ}$ A. Each Ba atom is surrounded by 18 Si atoms in an irregularly shaped polyhedron $@Si_{18}$. The polyhedra are connected by sharing faces to form Ba containing tunnels along the a axis. All of the Si-rich compounds so far with atomic ratios Si/Ba>2 in the binary system have been prepared only under high-pressure and high-temperature conditions. There is a general tendency that the Si/Ba ratio of the compounds increases with an increase of the pressure in the preparation.

Key words: Ba-Si System, BaSi₆, High-pressure Phase, Clathrate